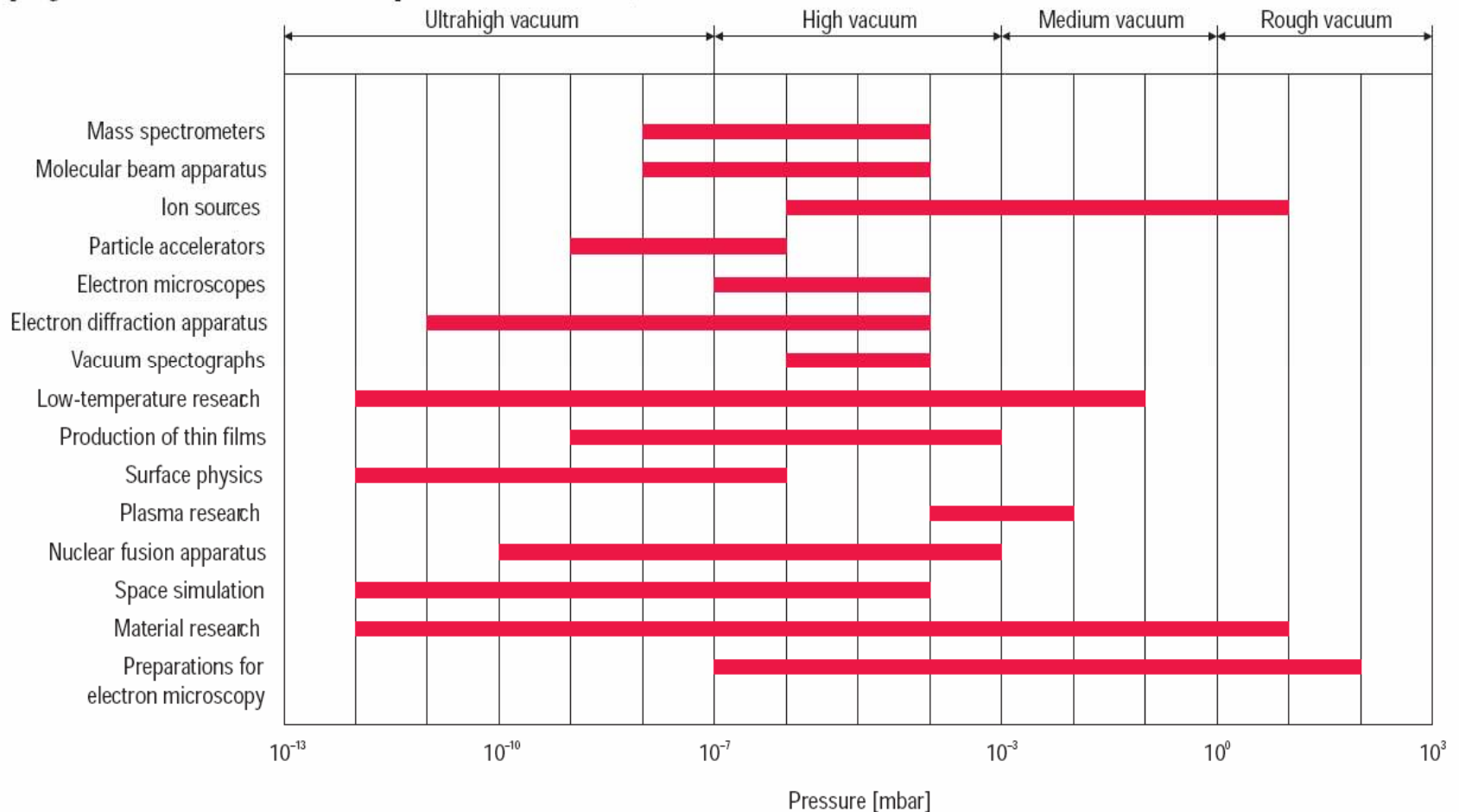


Industrial Applications of Vacuum

- overview applications of vacuum technology
- motivation of vacuum design in industrial applications
- examples of solutions in Coating
- example of solution in Process Industry
- examples of solutions in Analytical (mass spectrometry)
- outlook

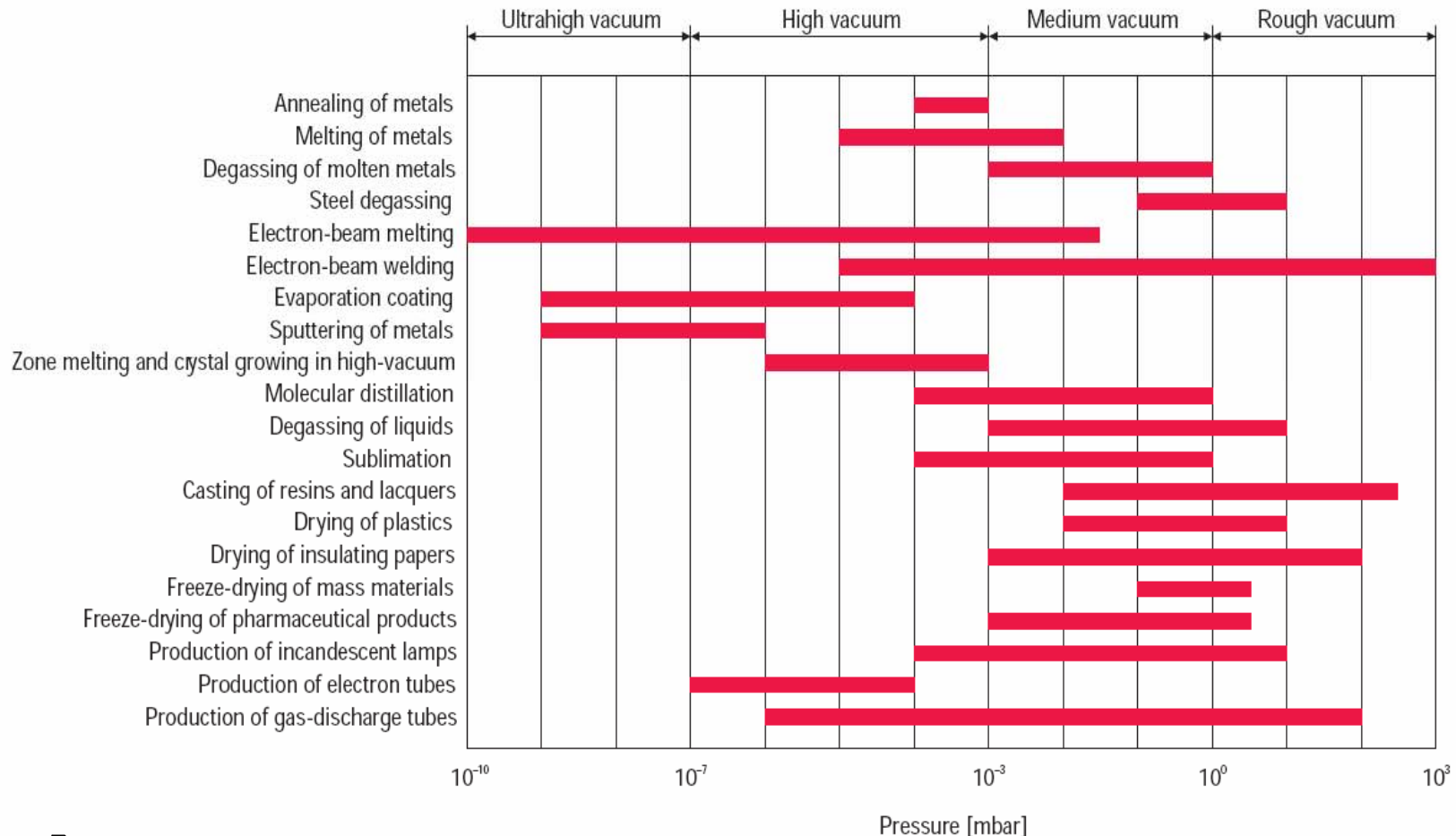
Pressure ranges of analytical methods

(physical and chemical; $p < 1000 \text{ mbar}$)



➔ **most analytical instruments require HV/UHV**

Pressure ranges of industrial vacuum processes



➔ the majority of industrial processes require fine vacuum

LEYBOLD VACUUM

Drivers for design of industrial vacuum system

(i.e. 90% of all systems)

- Analytical Instruments:
reach required vacuum quality within specified time
- Coating/Semiconductor/Process Industry
fulfill given production yield

system uptime

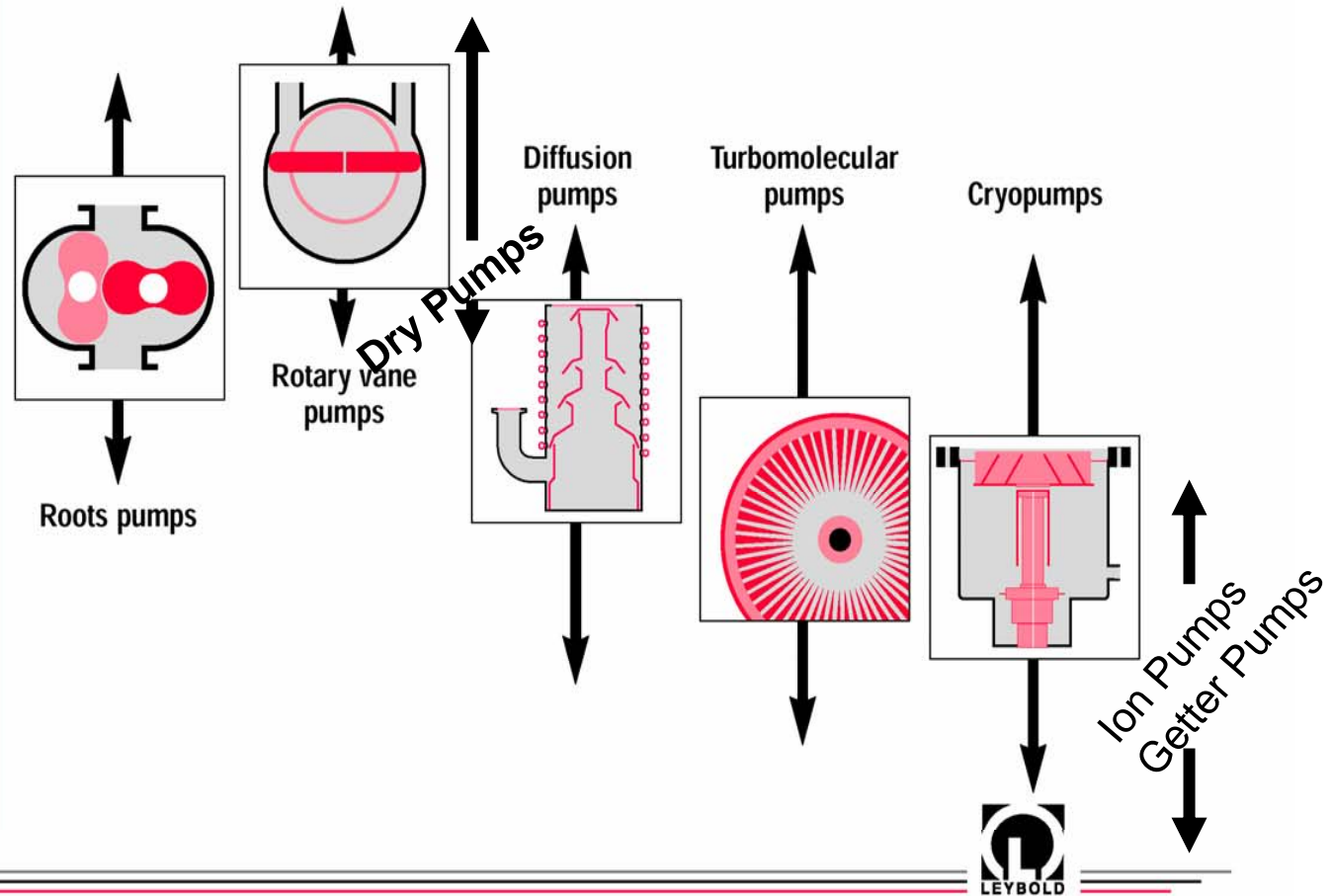
better vacuum performance only tolerated if better competitiveness
can be achieved (and paid by market)

reduction of manufacturing costs and/or lower CoO drive design
of machines after innovation phase

environment-friendly production

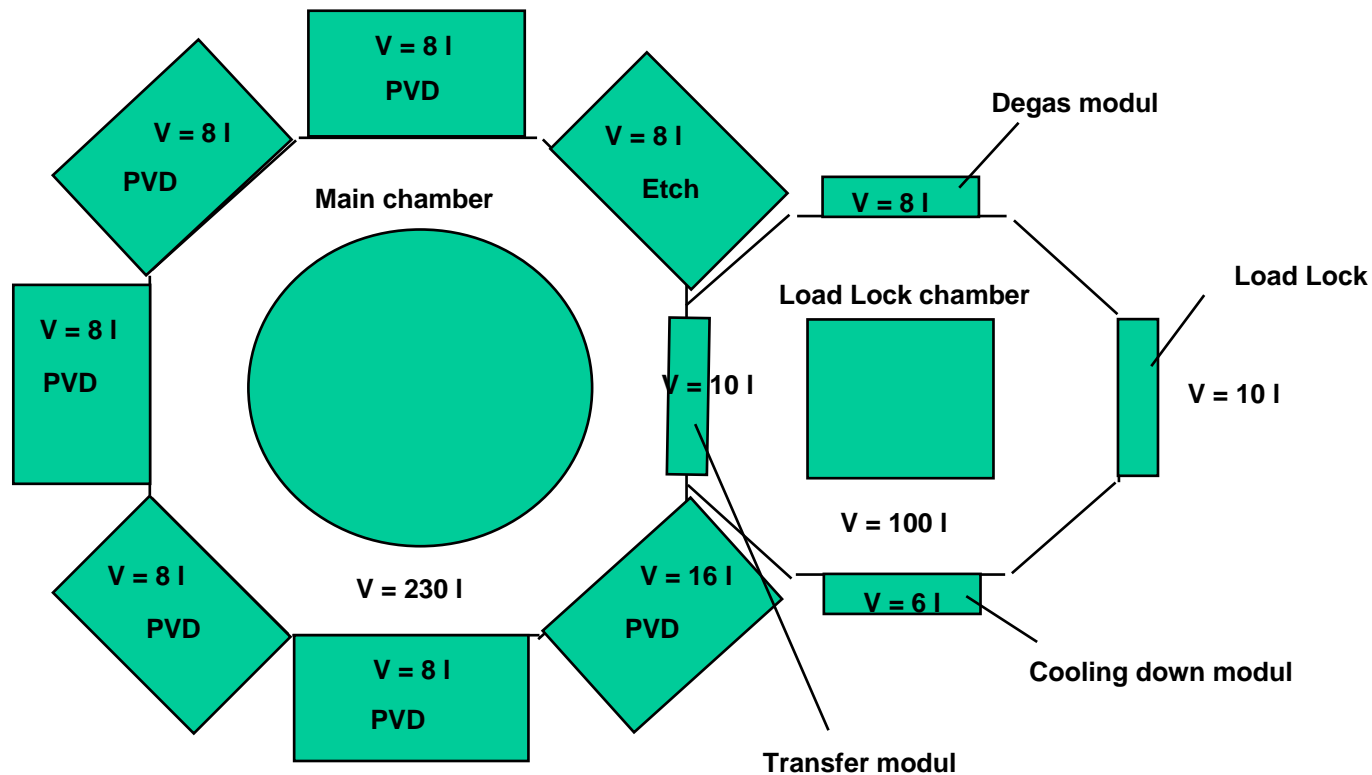
Vacuum pump technology for different pressure ranges

λ (m)	Height (km)	Pressure (mbar)
		1000 –
		100 –
10^{-5} –	20 –	10 –
	50 –	1 –
10^{-3} –		10^{-1} –
	100 –	10^{-2} –
10^{-1} –		10^{-3} –
10 –	200 –	10^{-4} –
		10^{-5} –
10^3 –	400 –	10^{-6} –
		10^{-7} –
10^5 –	800 –	10^{-8} –
		10^{-9} –
		10^{-10} –



Example Coating Industry

Layout of a coating system for 300 mm Wafers



market requirements



initial evacuation time to 1×10^{-07} mbar base pressure: < 24 hours

process time per wafer and process chamber: 30 s

pressure during sputtering: 6×10^{-03} mbar

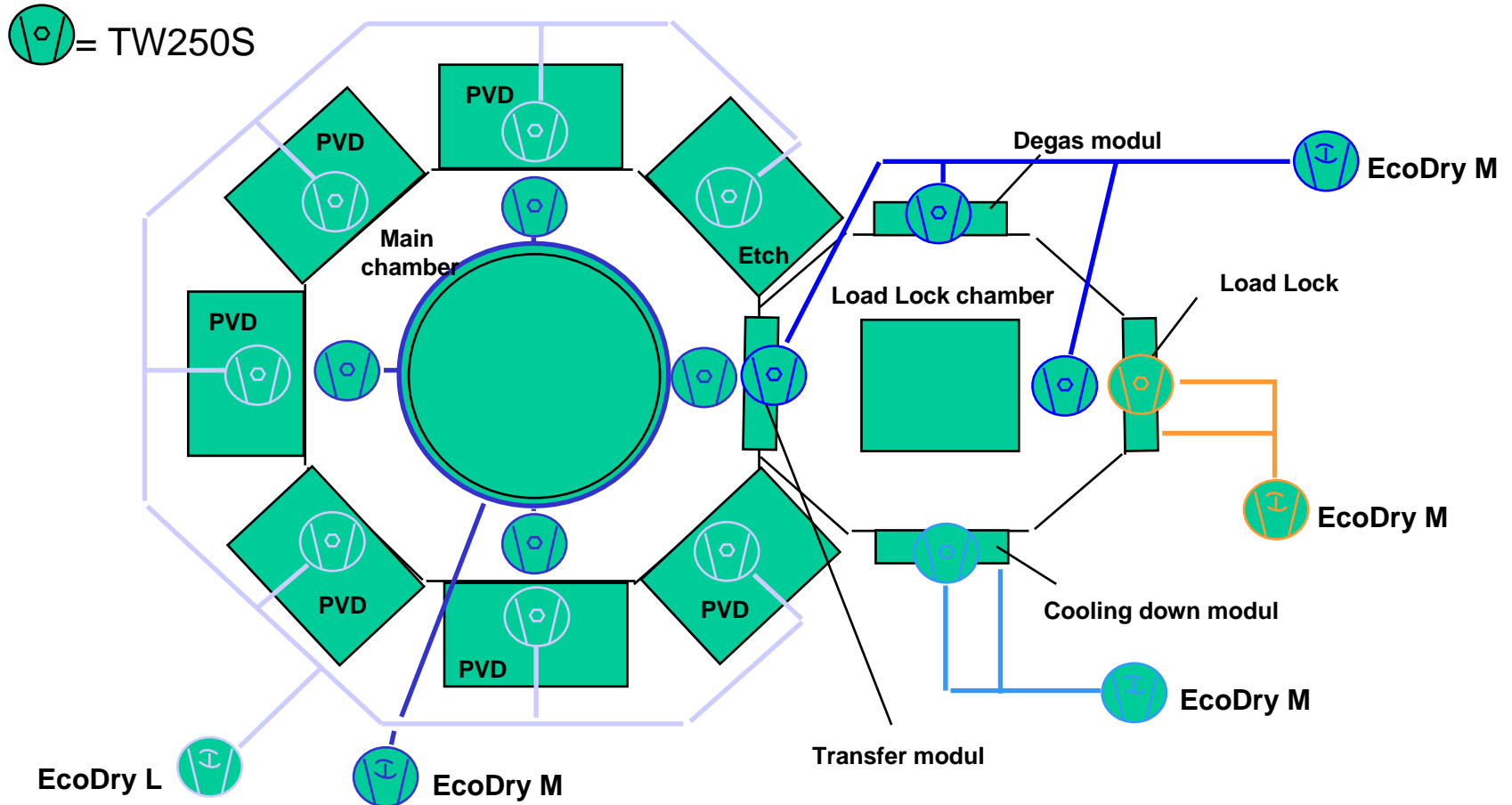
base pressure in main chamber during processing: < 1×10^{-06} mbar

Main chamber:

50% Aluminium, 50% stainless steel

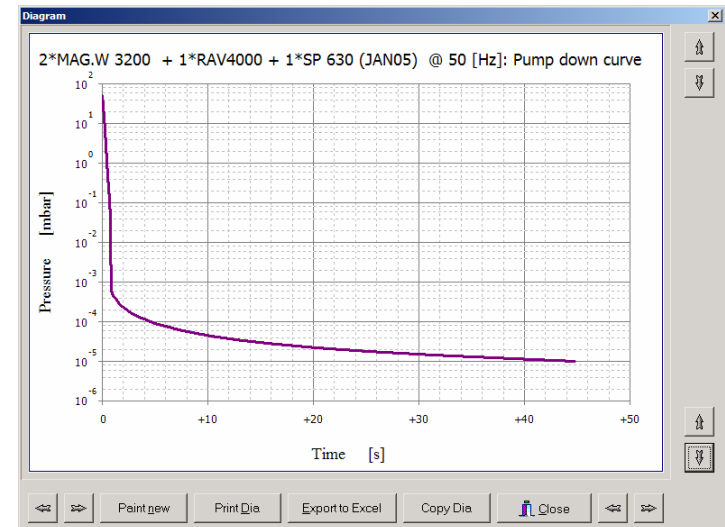
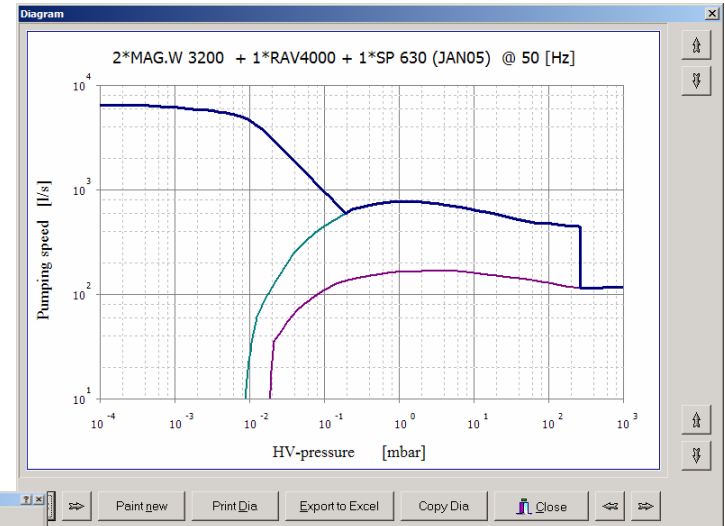
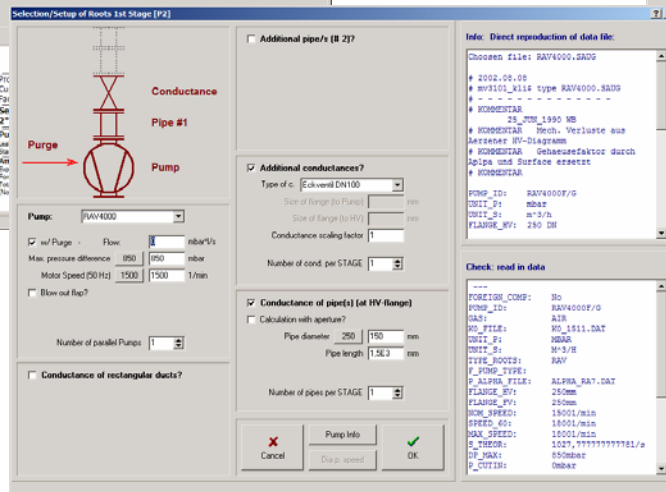
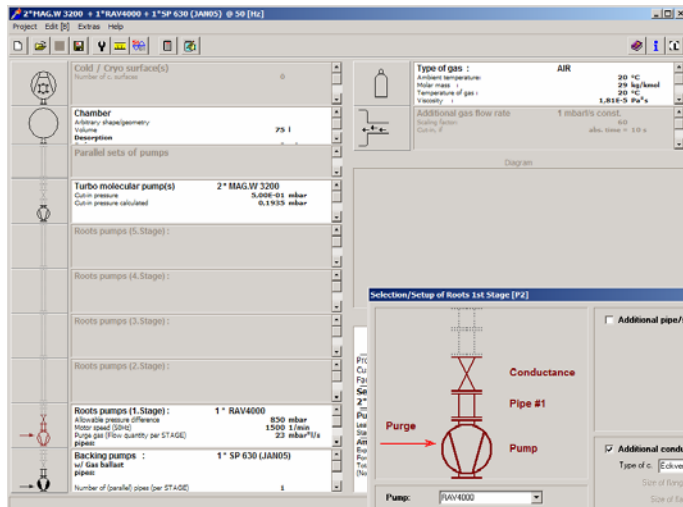
all other chambers: Aluminium

first draft of vacuum schematics:



necessary computing possibilities

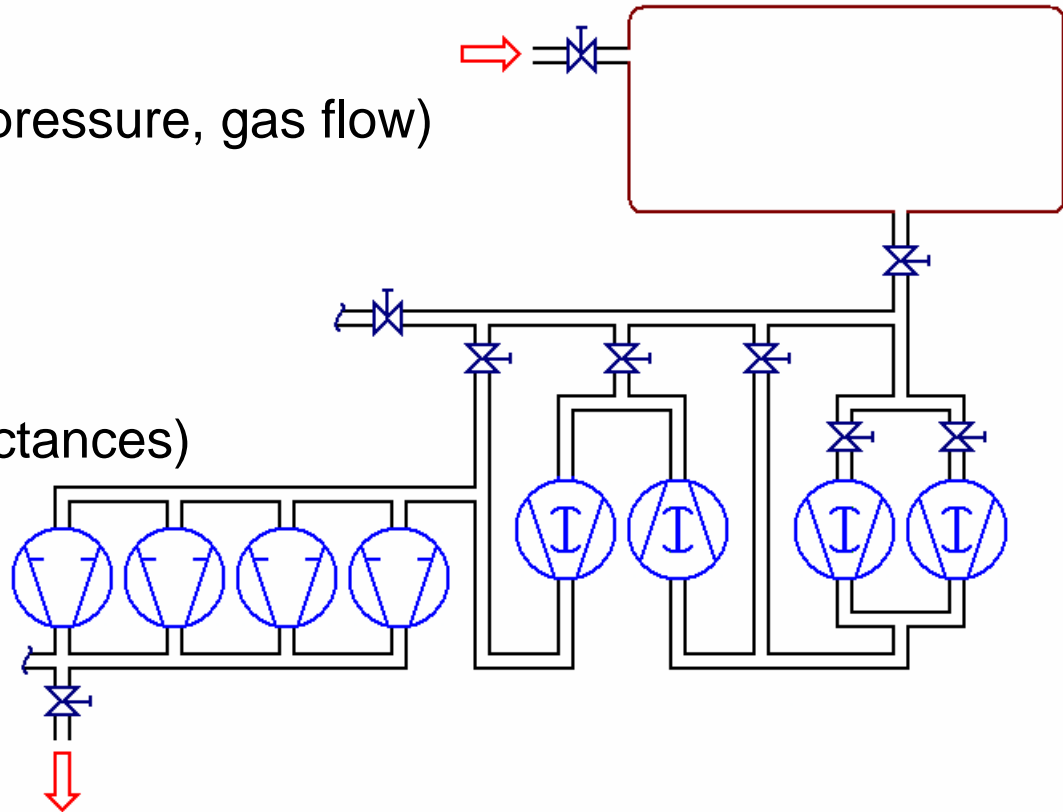
CompuVac © NT for Windows™



3 - Describing a vacuum system

Setup in principle:

- Chamber (Process: pressure, gas flow)
- Pump stages
- Components (conductances)
- (Medium)



3 - Describing a vacuum system: Pumps

A) Backing pumps

- pumping speed: $S = f(p_{HV})$

B) Roots pumps

- compression: $K = f(Q, K_0, p_{FV})$

C) High vacuum pumps (turbomolecular, diffusion, cryo)

- pumping speed: $S = f(p_{HV})$

D) Cryo surfaces

- pumping speed: $S = f(p_{HV})$

3 - Describing a vacuum system: Conductances

E) Pipes

- w/ or w/o apertures

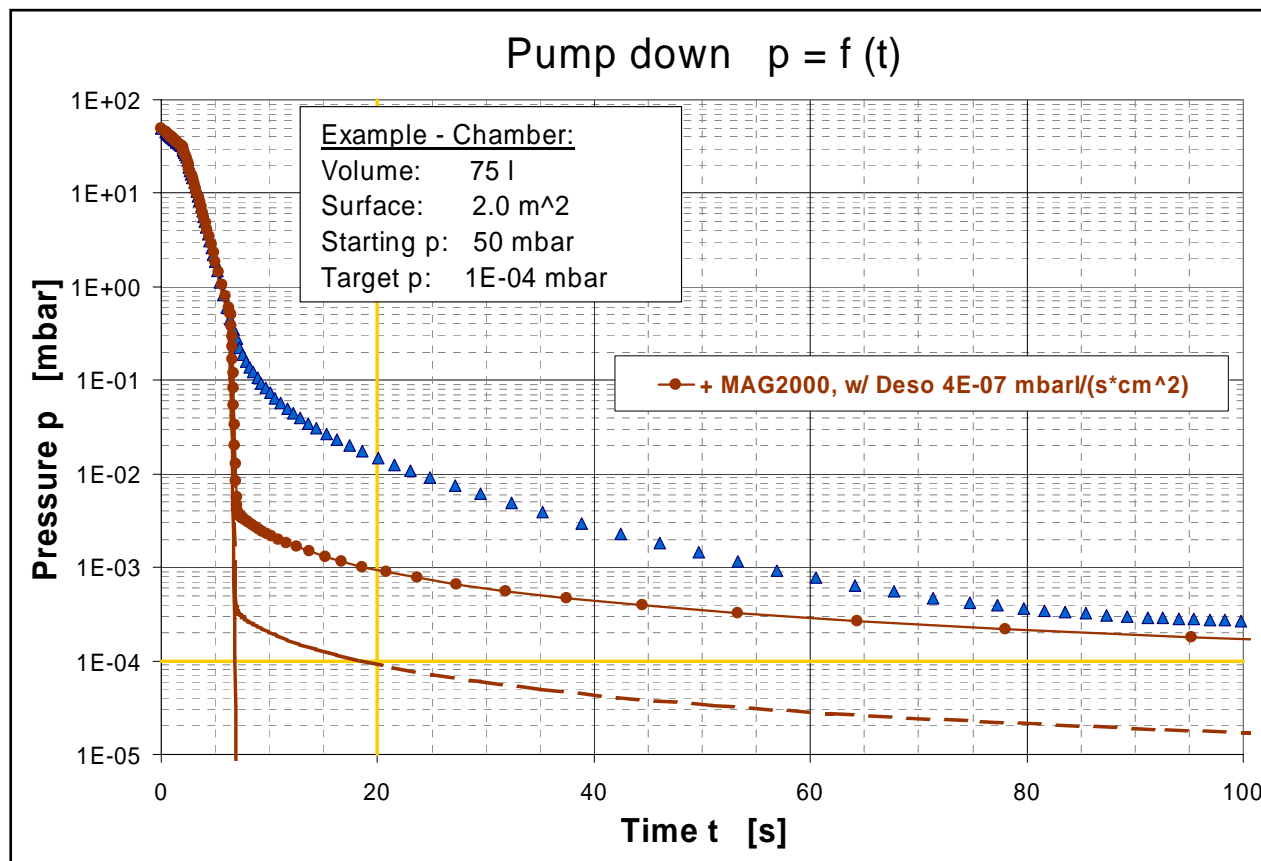
F) Rectangular ducts

- transformation into circular pipes; w/ or w/o apertures

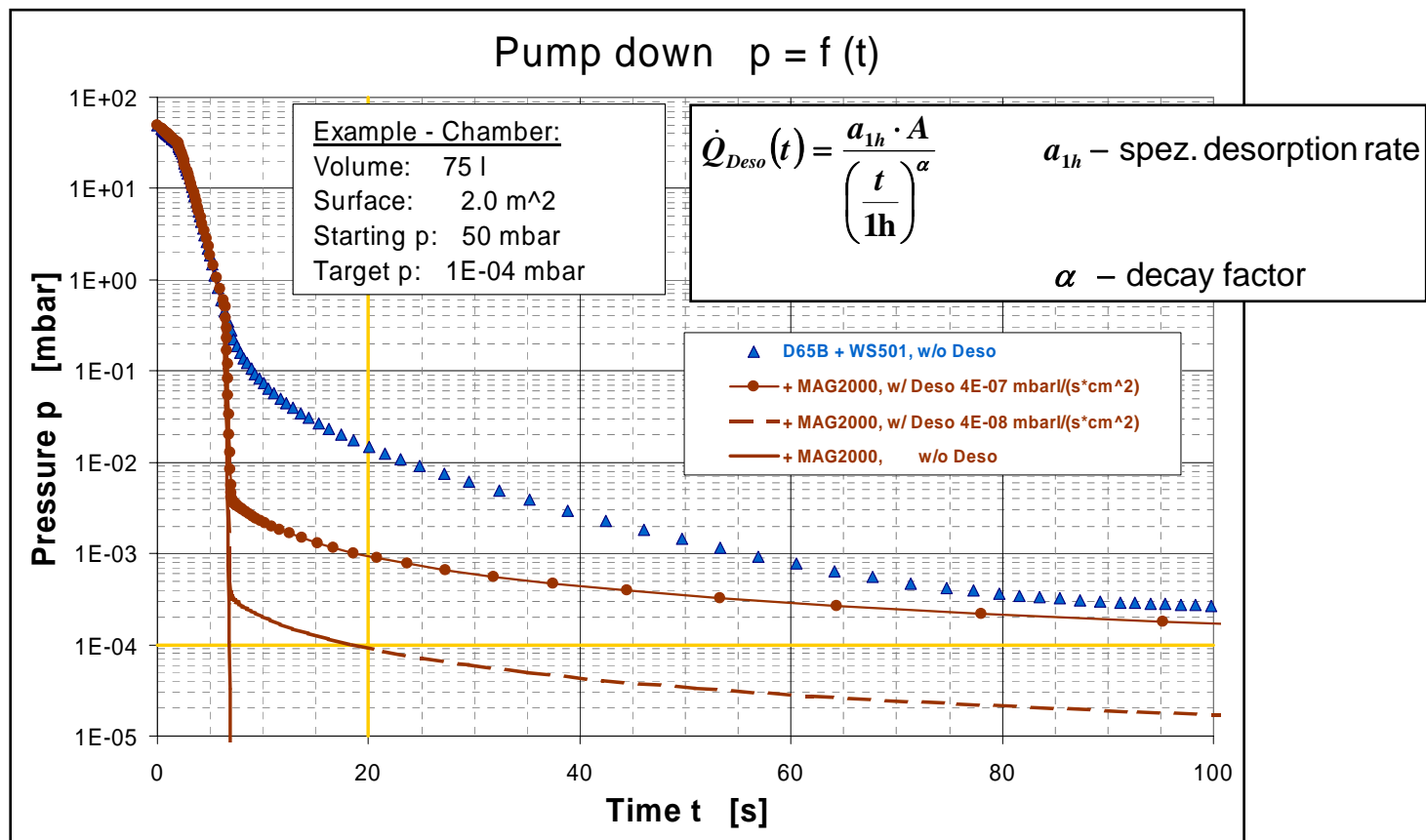
G) (Other) components - elbows, valves, filters..

- Transformation into circular pipe equivalents
- Direct function of conductance $C = f(p)$

4C - Influence: Gas load caused by desorption

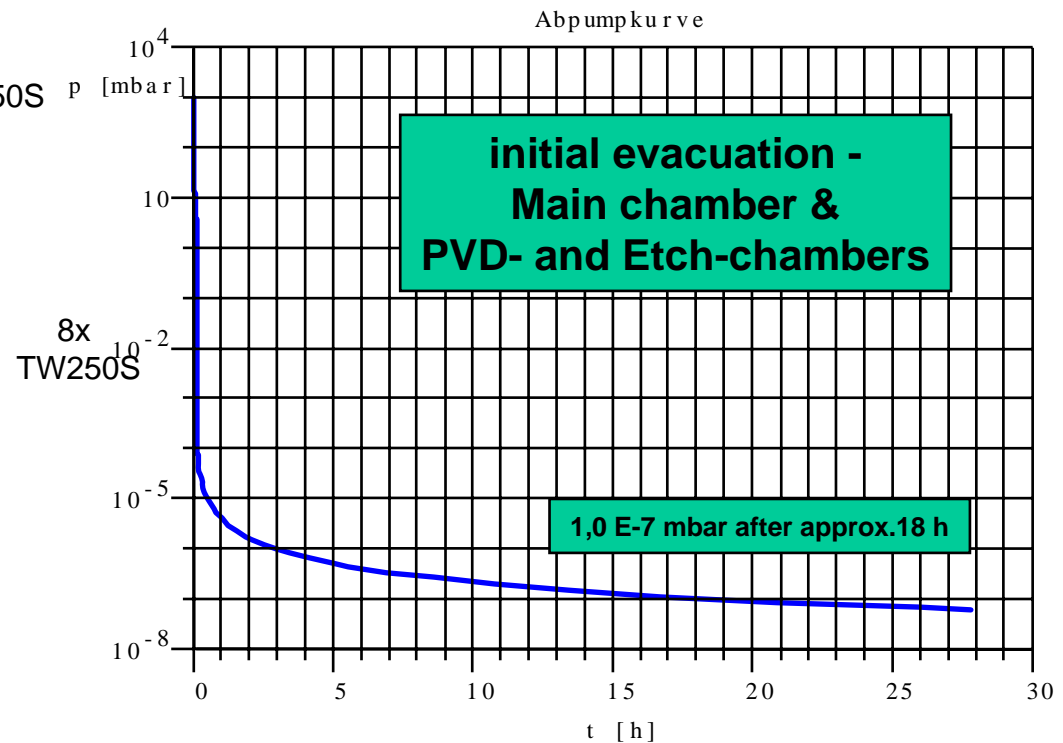
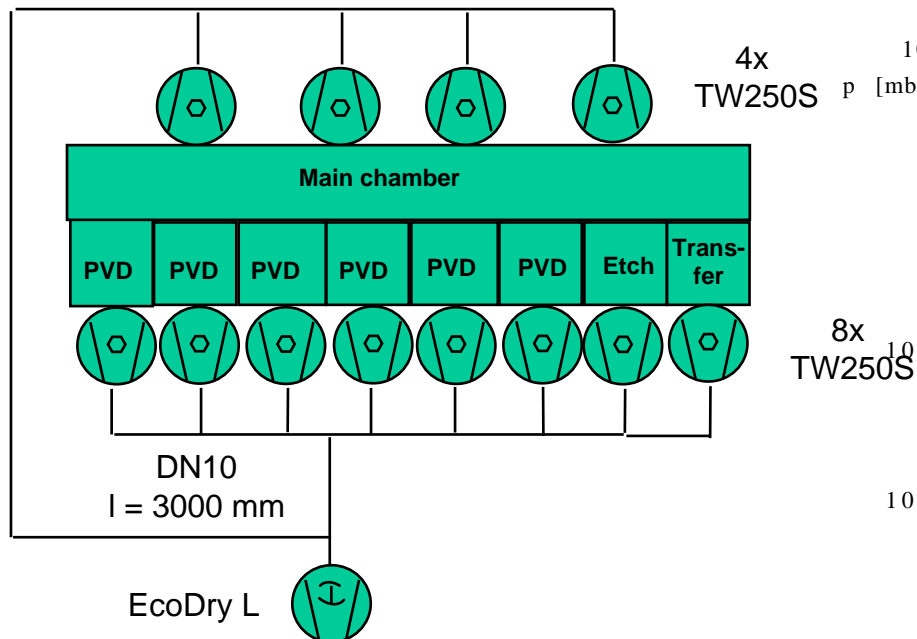


4C - Influence: Gas load caused by desorption



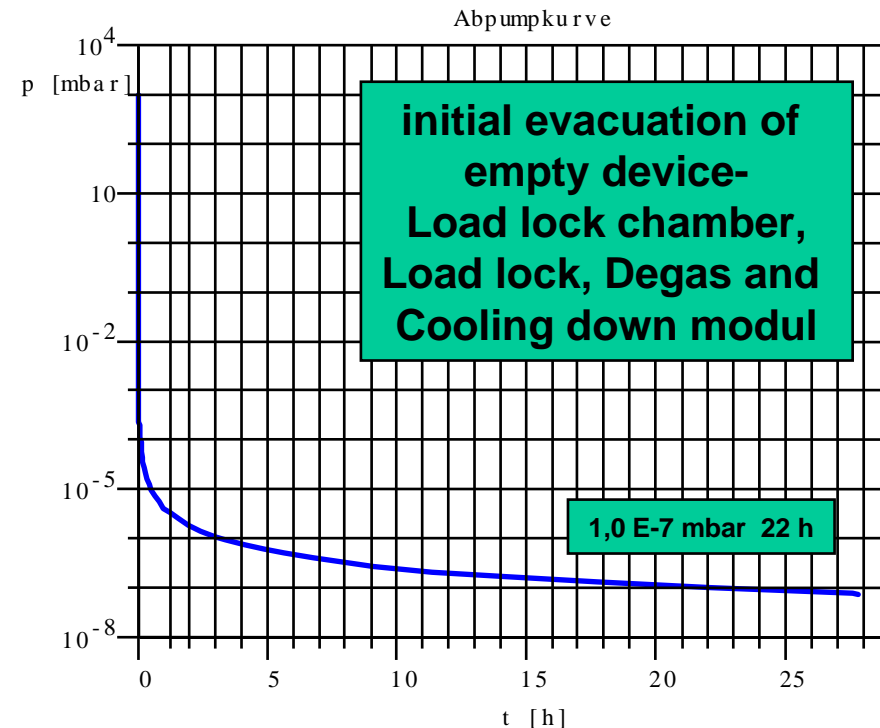
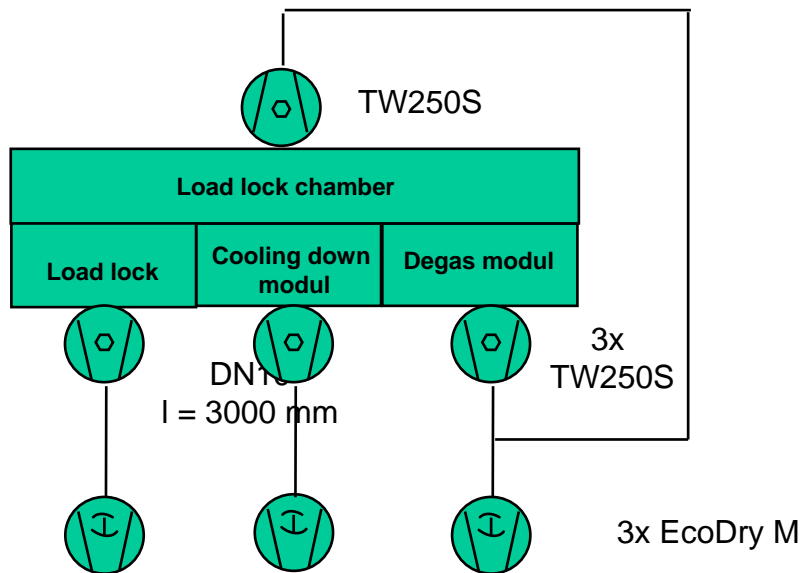
assumptions: degassing rates
steel 2×10^{-08} mbarl/scm²
aluminium 6×10^{-08} mbarl/scm²
no further desorption, permeation, or leaks

calculation model:



conditioning of Load Lock chamber, Degas module, Cooling down modul

calculation modell:



➔ positive results calculated for empty chamber

next step: chamber loaded with wafer

pressure in main chamber loaded with wafer

at different degassing rates

Desorptionsrate des Wafers

beim Beladen der Load Lock: $q = 2E-7 \text{ mbarl/s*cm}^2$

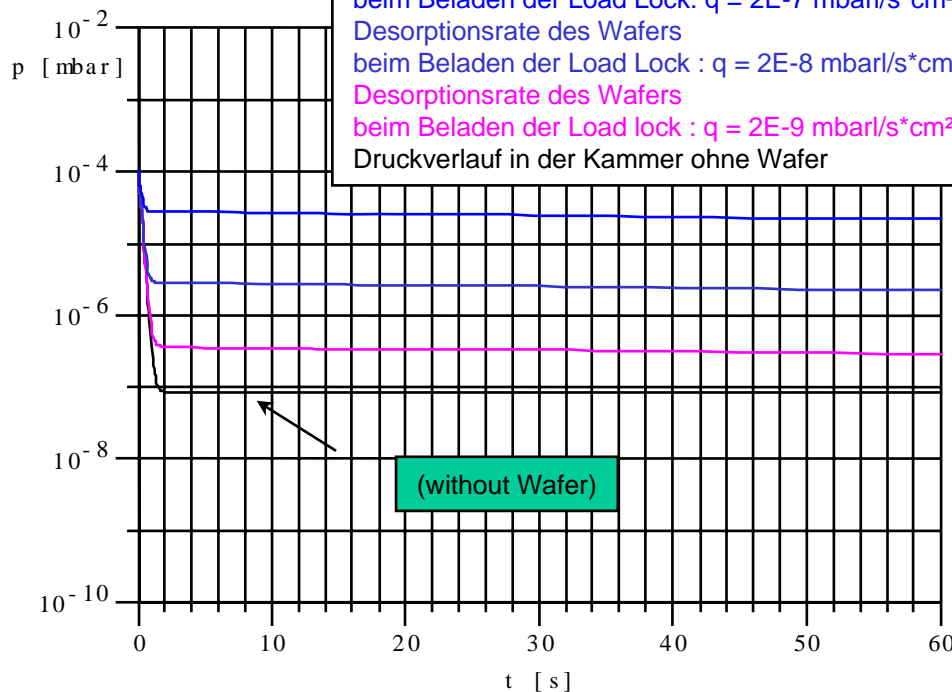
Desorptionsrate des Wafers

beim Beladen der Load Lock : $q = 2E-8 \text{ mbarl/s*cm}^2$

Desorptionsrate des Wafers

beim Beladen der Load lock : $q = 2E-9 \text{ mbarl/s*cm}^2$

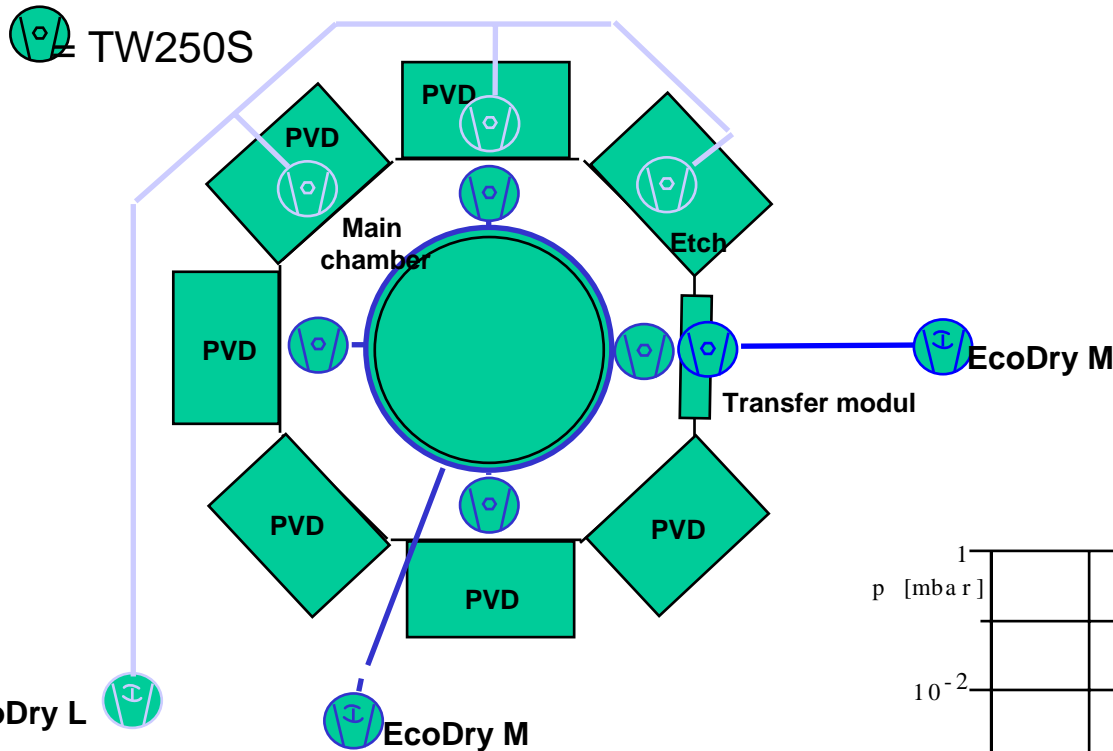
Druckverlauf in der Kammer ohne Wafer



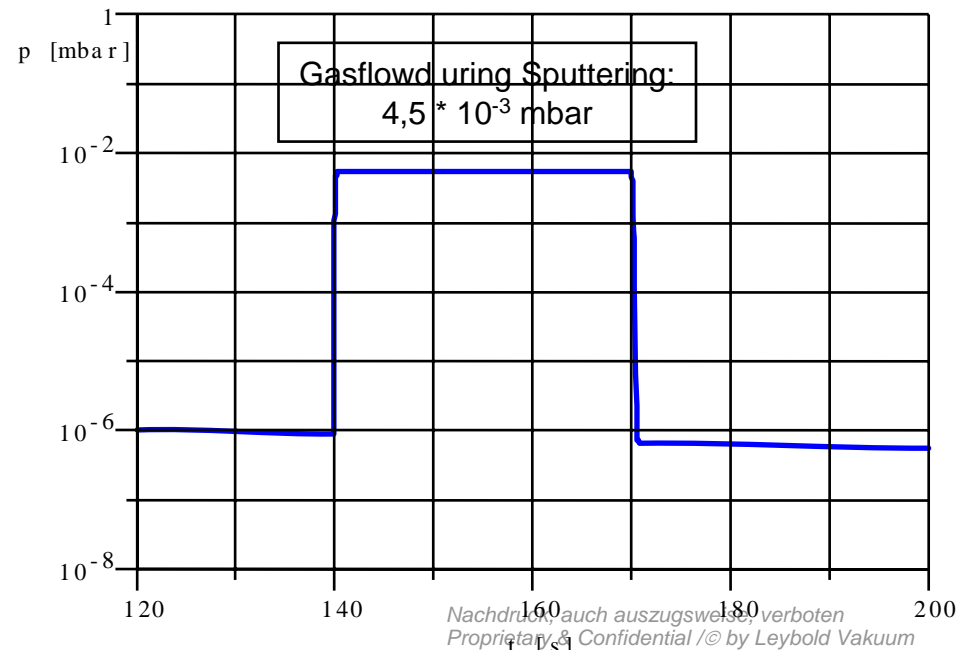
degassing rate of wafer will decline during time in chamber

- ➔ high impact from unknown/non-reproduceable degassing rate of wafer
- ➔ degas module highly recommended

next step: manufacturing of laboratory device without load-lock chamber



results:
cycle times verified
pumps achieve specified pressures
degassing chamber necessary



finally: picture of a commercial machine



Picture: Unaxis, Data Storage Coating System

short movies:

[data storage](#)

[web coating](#)

Typical industrial applications in Process Industry

- Industrial Furnaces
- Metallurgical Systems
- Coating
- Packaging
- Distillation
- Drying



Distillation



Leak Testing



Re-melting of special alloys



Heat Treatment



Cleaning and Vacuum Drying

Typical environment for industrial vacuum pumps

- High dust or particle load
- Corrosive media can enter pump
- Vapors (e.g. water, oil, fluxing agents, waxes, resins, oligomers) need to be pumped
- Pumping of pure Oxygen gets more usual, e.g. in Coating applications



O₂

Application Example

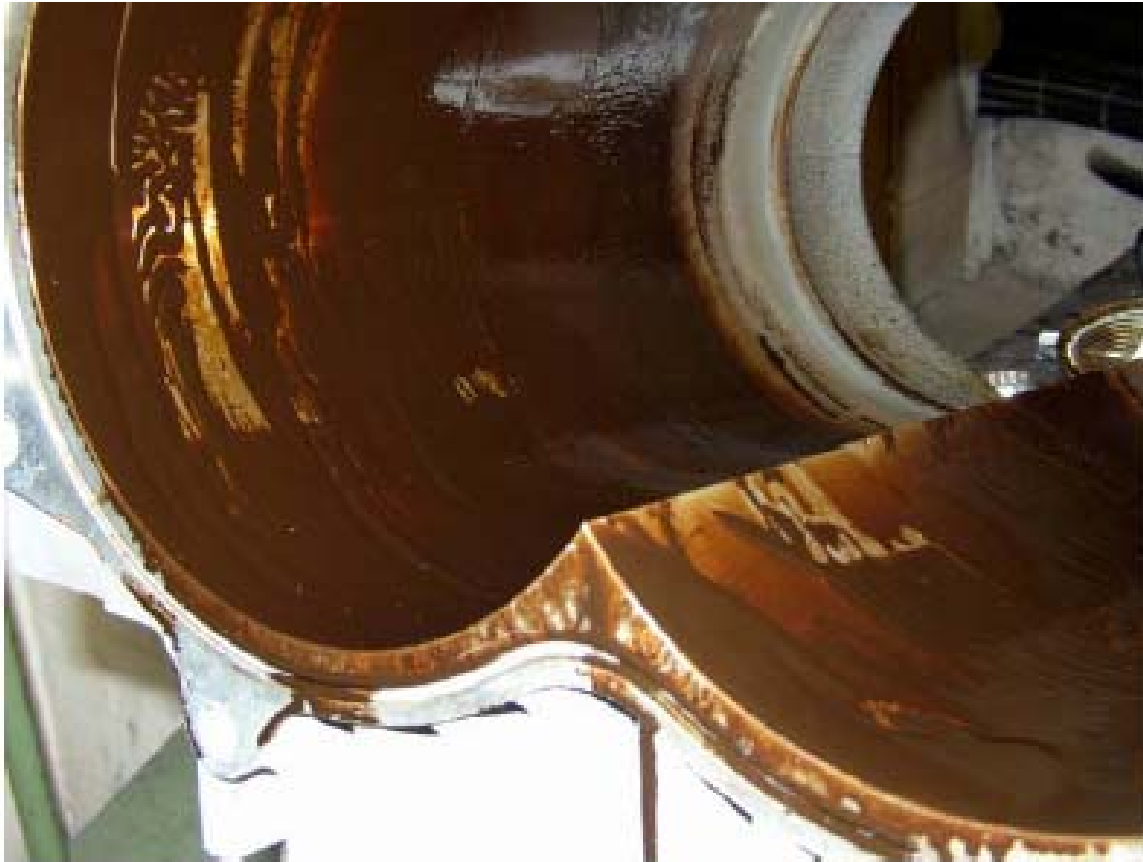
Vacuum Sintering of cutting tools

Sintering of cutting tools.
Dewaxing process under vacuum.



Vacuum Sintering of cutting tools

PEG used as binding material is found within the pumping chamber and the rotors. Rotary Vane Pumps failed due to accumulation of this material inside the oil circuit.



Vacuum Sintering of cutting tools



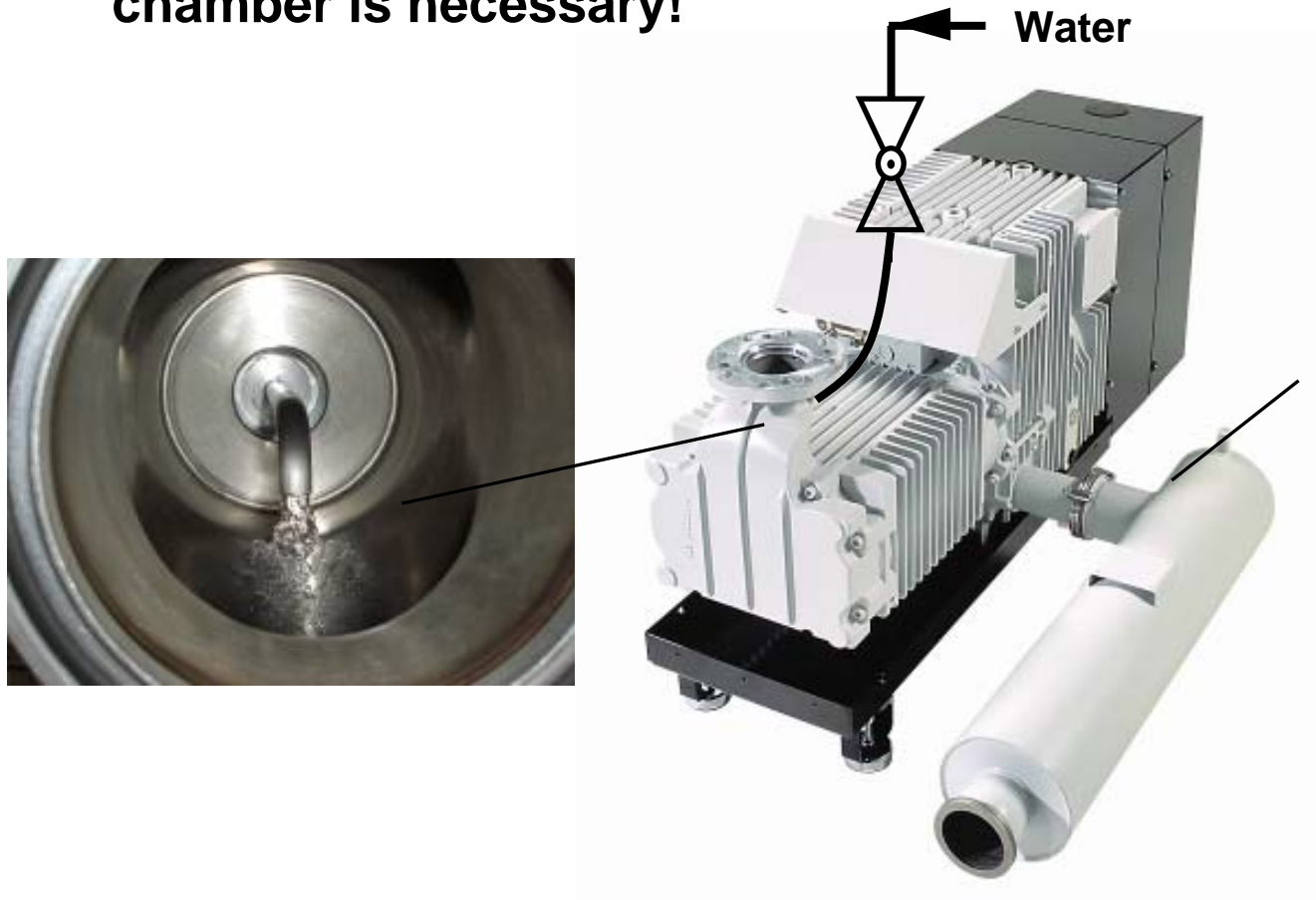
Rotors and pumping chamber can be cleaned manually by acetone which is reasonable for infrequent cleaning (6 – 8 weeks)

Dismantling the pumping chamber is necessary.

Vacuum Sintering of cutting tools

For frequent cleaning purpose a flushing kit can be used when rotors turning.

No dismantling of the pump chamber is necessary!



Vacuum Sintering of cutting tools



Before cleaning



**Cleaning results after
flushing with 8 litres water.**

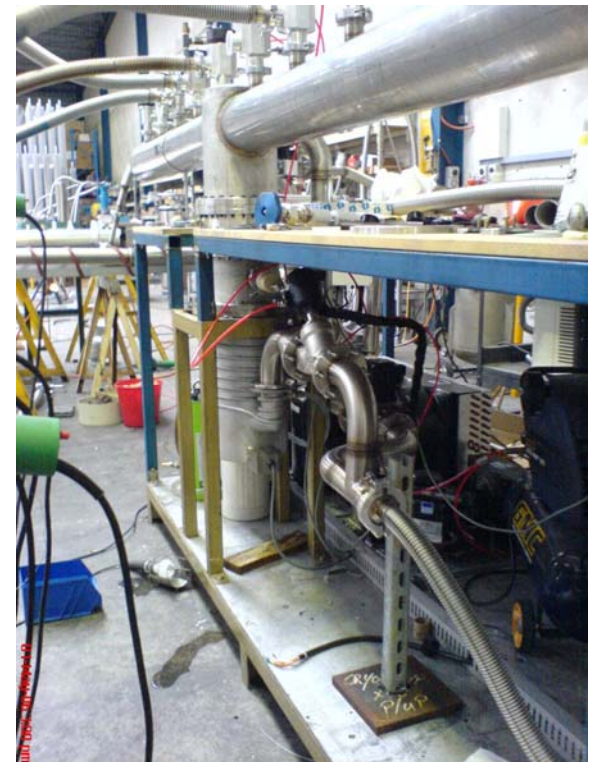


After cleaning

➔ Dry pump can handle process related layers!
Manual cleaning or flushing are possible!

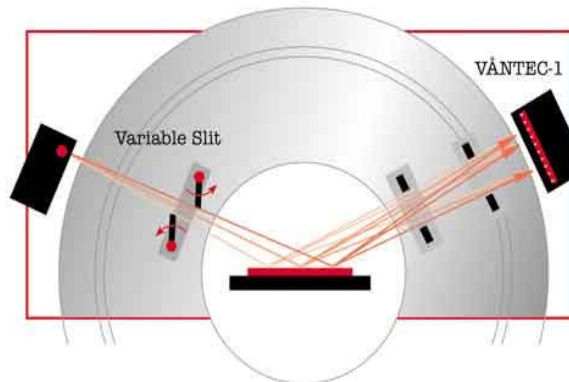
education level in industry may be lower than in
large research facilities

example: conductance losses unknown in evacuation of cryogenic lines?



Typical Analytical Instruments

- Mass Spectrometers
- Electron Microscopes
- X-Ray Analyser



Vacuum Pumps for Analytical Instruments

Definition :

Analytical Instruments are used to investigate and identify substances and/or structures.

Vacuum is needed

- to isolate the species from the environment in order to get a clear signal. The lower the pressure, the better;
- to produce the necessary free length of path in order to achieve high resolution images and spectra or to warrant the required lifetime of the electrodes at X-ray guns

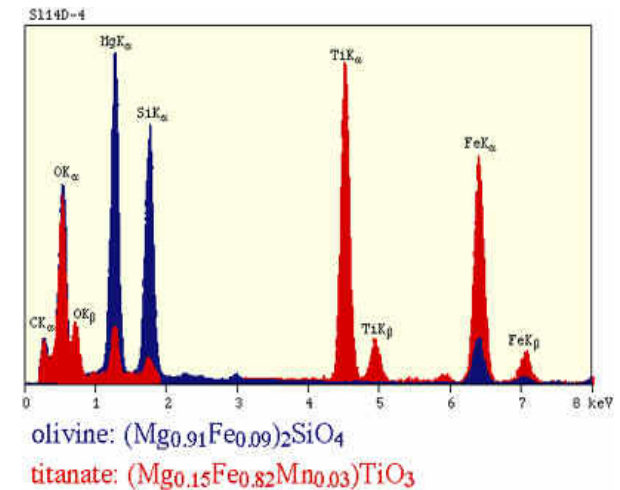
Vacuum Pumps for Analytical Instruments

Some Applications for Analytical Instruments

		Mass-Spectrometer	Electron Microscopes	Leakdetector	X-ray analyser
Health Care	Genomics				
	Proteomics				
	Drug Discovery				
	Metabolism				
Defense / Security	Bomb Detection				
	Forensic				
Quality Control	Semiconductor				
	Automotive				
	Food				
	Environmental Control				
the sum of the processes in the buildup and destruction of protoplasm			Mapped the human genome and develop new drugs based on their research		
			separation and identification of proteins		

Vacuum Pumps for Analytical Instruments

Mass Spectrometer: Defined as a machine, that determines what substances are and/or how much there is



**Sample of
substance**



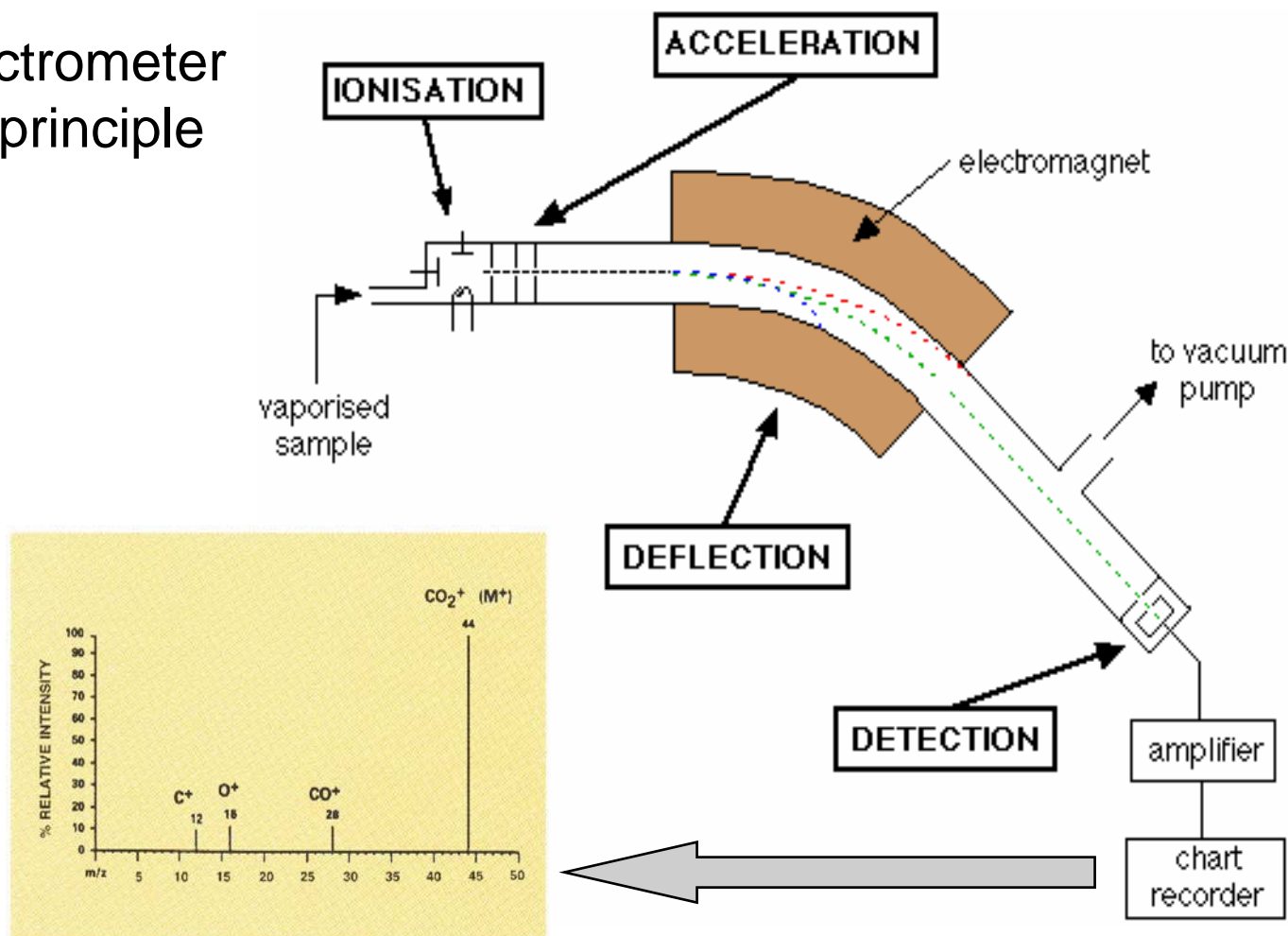
**Mass
Spectrometer**



**What it is and
how much**

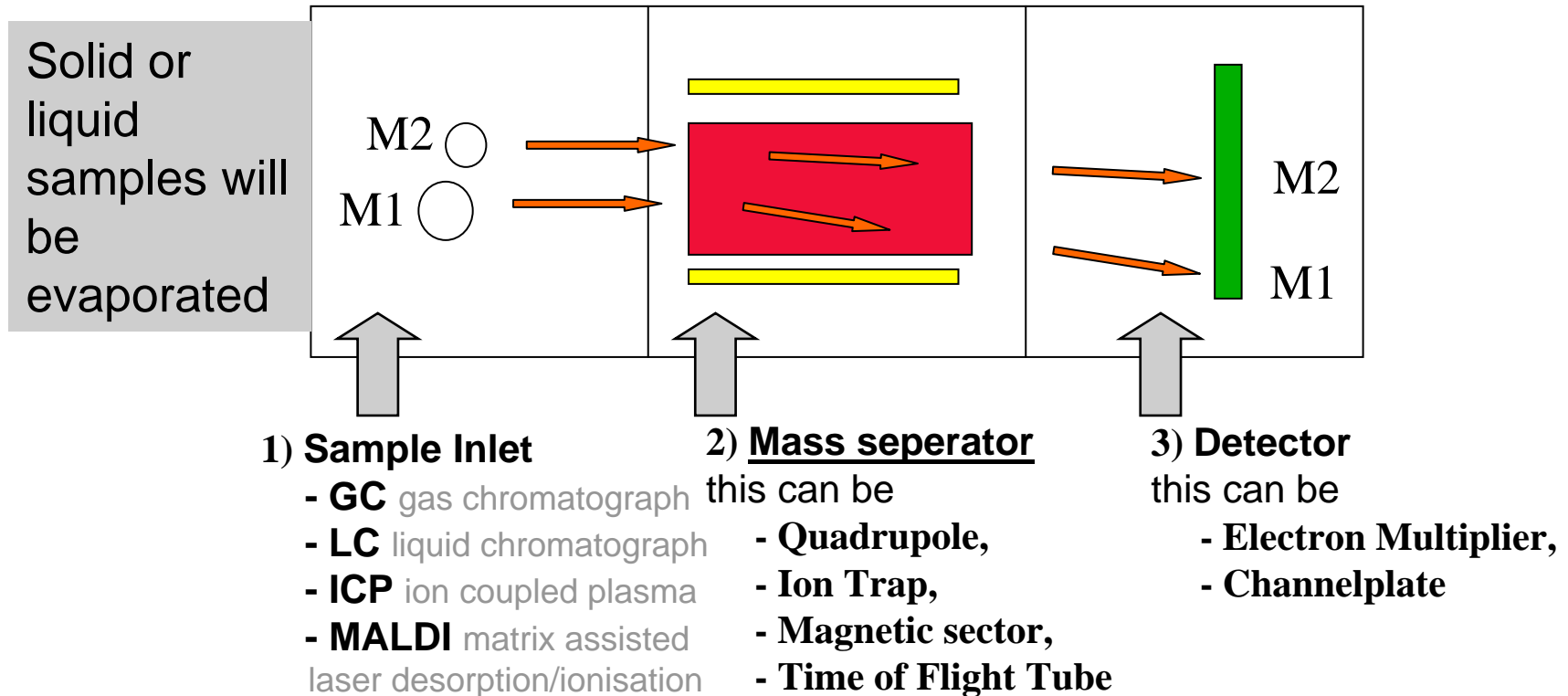
Vacuum Pumps for Analytical Instruments

Mass Spectrometer
functional principle



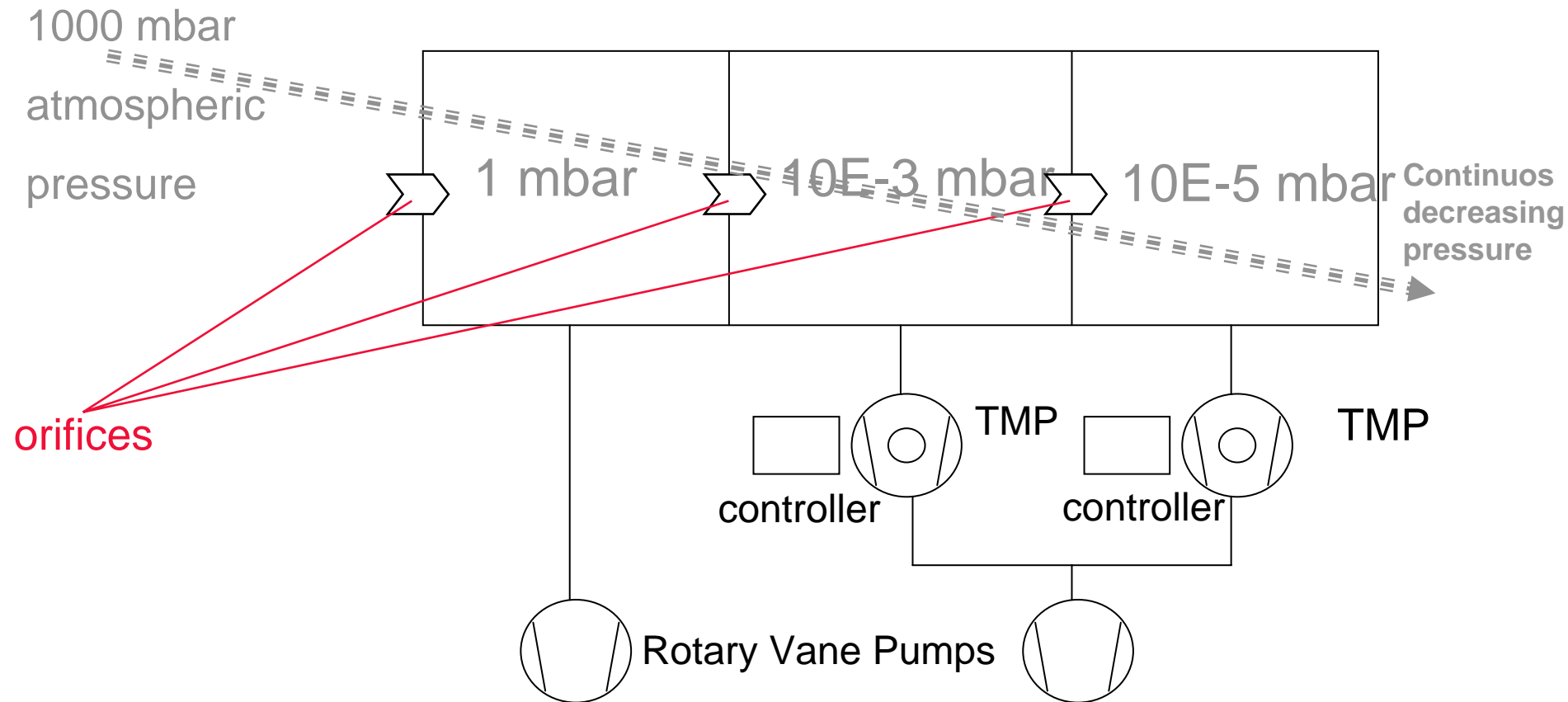
Vacuum Pumps for Analytical Instruments

Mass Spectrometers consist of 3 main components



Vacuum Pumps for Analytical Instruments

Typical Vacuum Schematic of a Mass Spectrometer



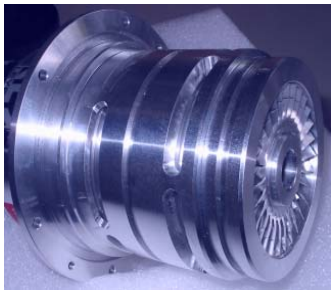
Vacuum Pumps for Analytical Instruments

Special Vacuum Pumps for Mass Spectrometers

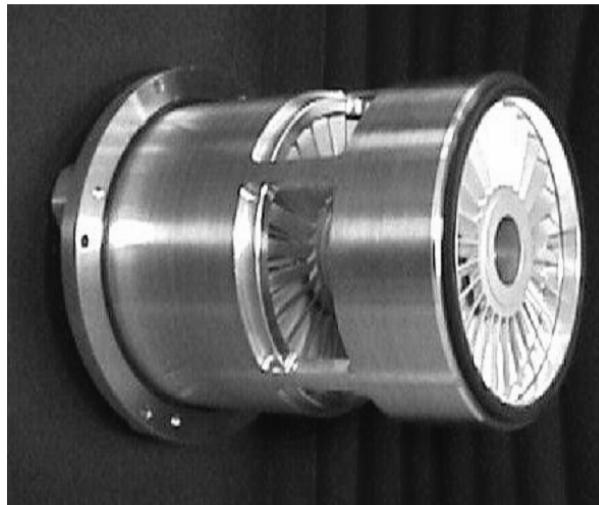
1 mbar

10E-3 mbar

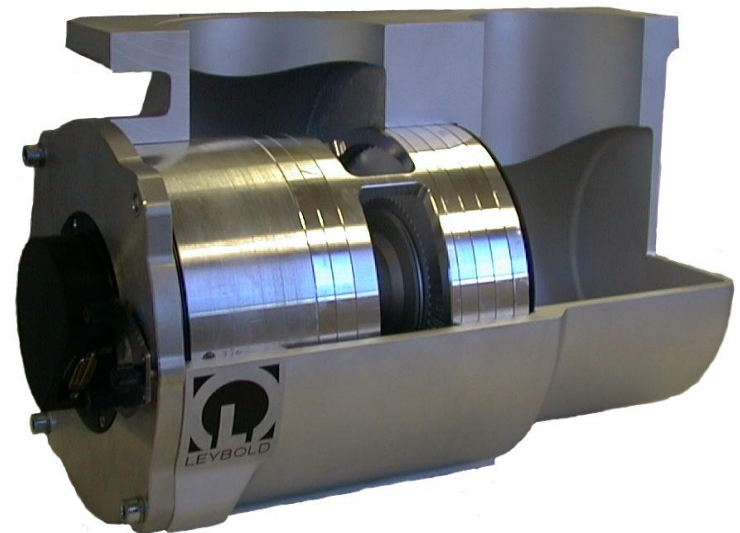
10E-5 mbar



TW
70LS
cartridge



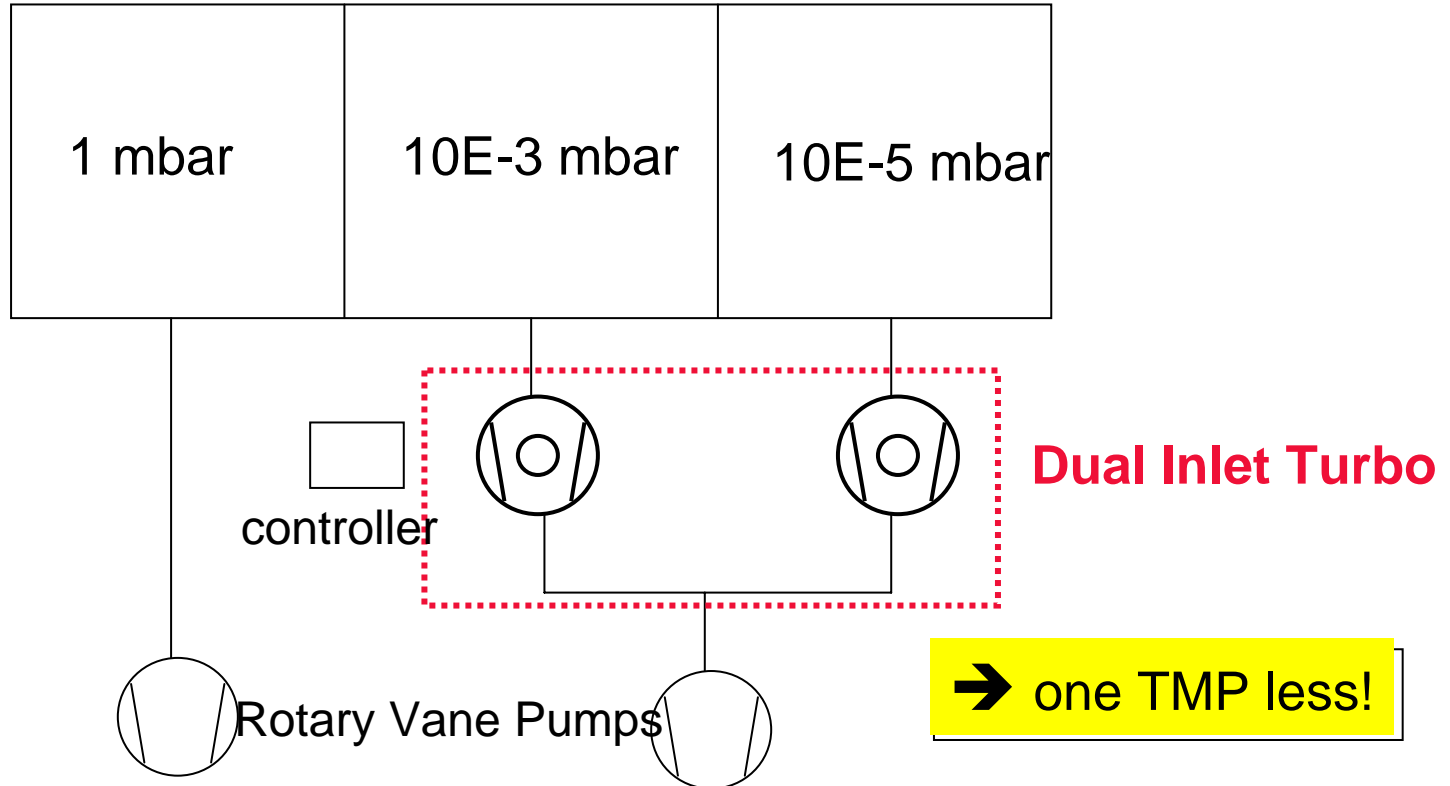
TW 220/150
cartridge



TW 220/150
with customised housing

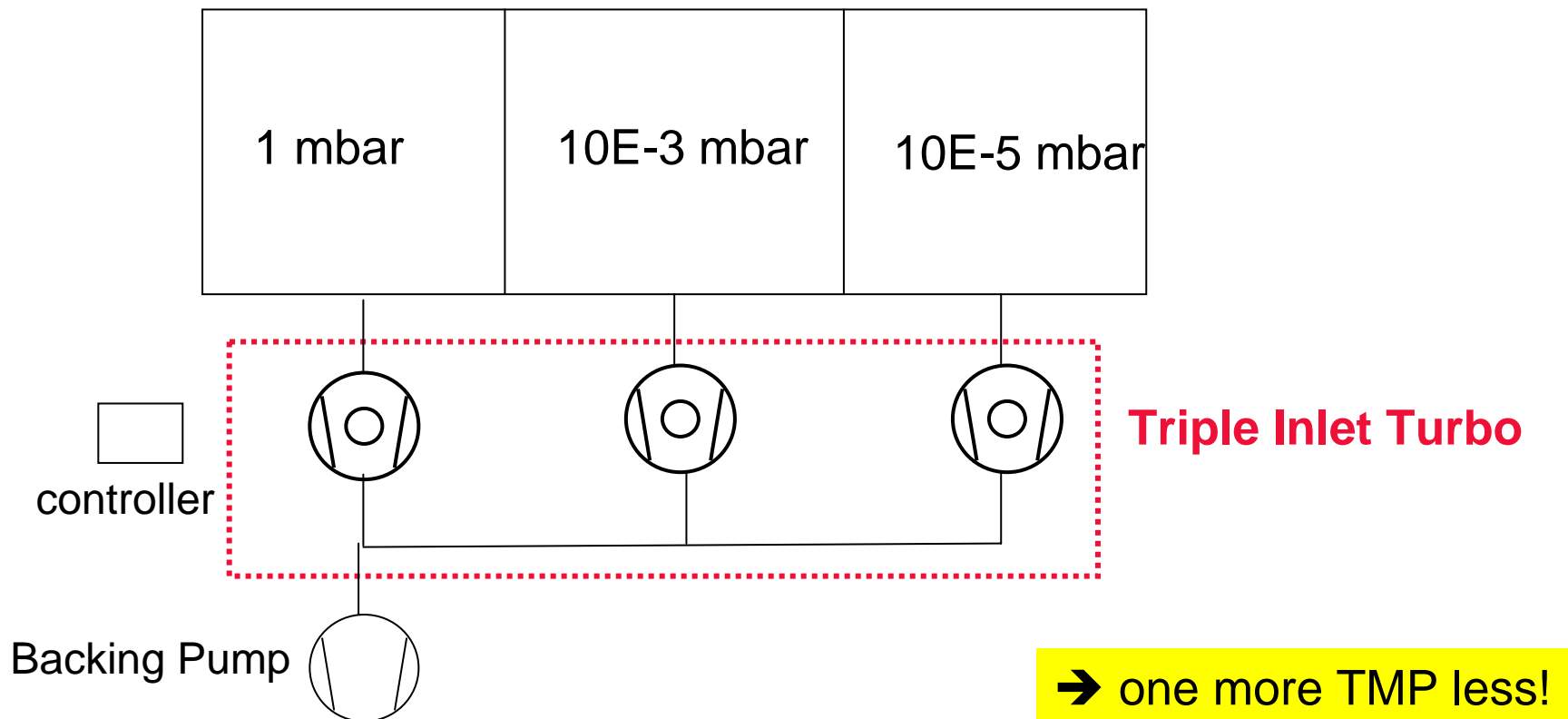
Vacuum Pumps for Analytical Instruments

customer requirement: cost/size/weight – reduction:
(Multiple Inlet Turbo)



Vacuum Pumps for Analytical Instruments

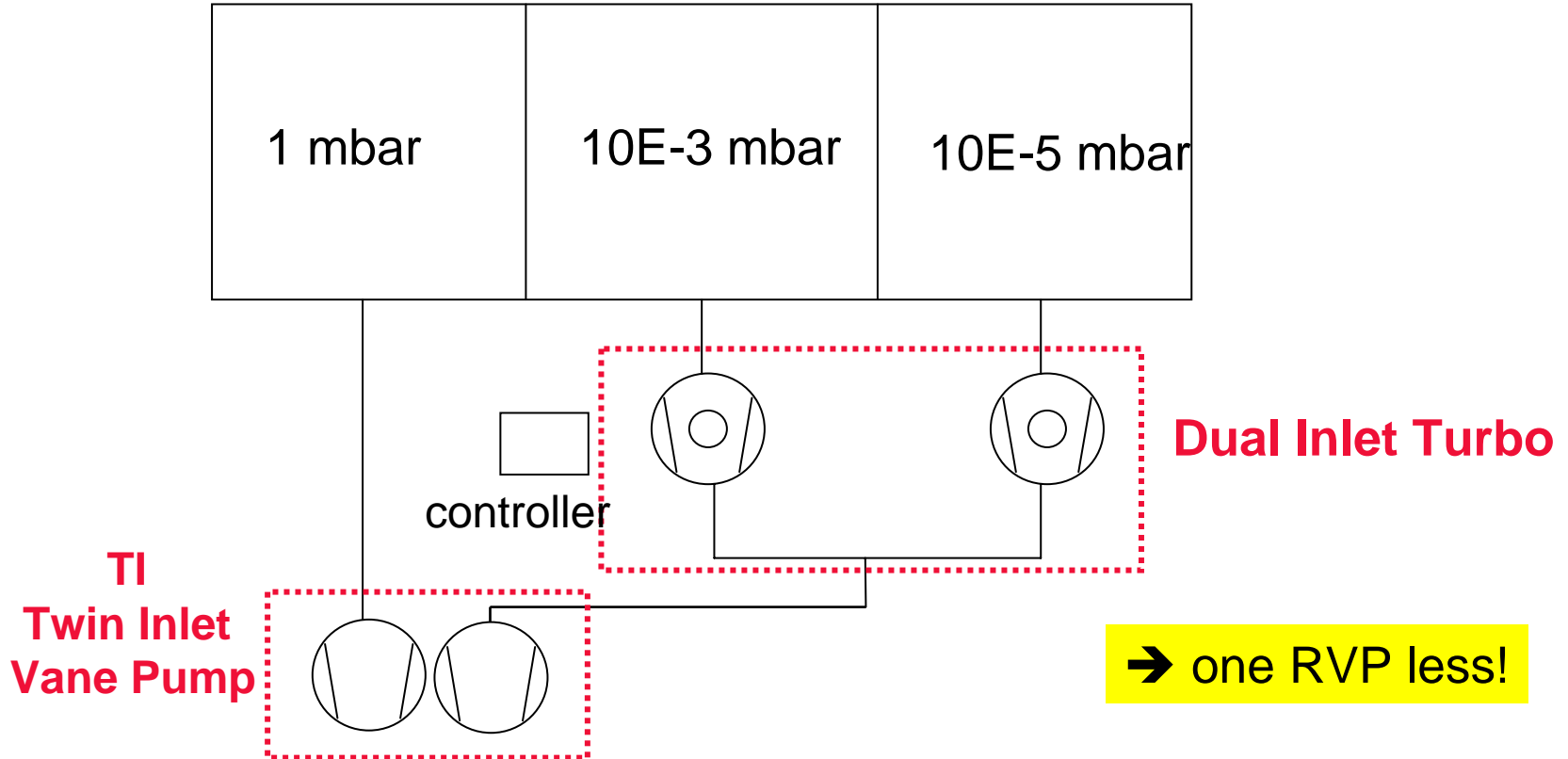
Typical Vacuum Schematic (Multiple Inlet Turbo)



→ one more TMP less!

Vacuum Pumps for Analytical Instruments

Typical Vacuum Schematic (Multiple Inlet Turbo and Twin Inlet Vane Pump)



Vacuum Pumps for Analytical Instruments

Typical Vacuum Pumps for a Mass Spectrometer

TW 220/150
with customised
housing
integrated into a MS
of Thermofinigan

displayed on
ANALYTICA show
Munich 2004



Thank You !